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Appln. No: 10/705,805	Atty: Jean-Paul G. Hoffman/R. Parra
First Inventor: JOERI LOF	Date: June 2, 2004
Title: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD	Attorney Docket No: 081468-0306781

**ENCLOSED:**

- ☒ IDS Letter
- ☒ Cited Applications
- ☒ PTO-1449
- ☒ Cited Documents

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FORM PTO-1449 (modified)  
To: U.S. Department of Commerce  
(PW FORM PAT-1449)  
Patent and Trademark Office

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Client Ref

306781

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**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**

Applicant: LOF et al.

Appln. No.: 10/705,805

Filing Date: November 12, 2003

Date: June 2, 2004

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of

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Examiner:

Group Art Unit: 1756

**U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR	2004/0075895 A1	LIN			
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					

**FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name		English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
	IR	JP 07-132262	05/1995	JAPAN	HIRAKAWA <i>et al.</i>	X			
	JR	JP 58-202448	11/1983	JAPAN	KAWAMURA <i>et al.</i>	X			
	KR	WO2004/019128	03/2004	PCT	OMURA <i>et al.</i>				
	LR	WO 03/077037	09/2003	PCT	ROSTALSKI				
	MR	WO 03/077036	09/2003	PCT	SCHUSTER	X			
	NR	DD 206 607	02/1984	GERMANY	WESTPHAL <i>et al.</i>		X		
	OR	DD 221 563	04/1985	GERMANY	PFORR <i>et al.</i>		X		
	PR								
	QR								

**OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

	RR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
	SR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
	TR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
	UR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521			
	VR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
	WR	B. LIN, "The $k_3$ coefficient in nonparaxial $\lambda/NA$ scaling equations for resolution, depth of focus, and immersion lithography, <i>J. Microlith., Microfab., Microsyst.</i> 1(1):7-12 (2002)			
	XR				
	YR				
	ZR				

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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